

ABSTRACT OF THE DISCLOSURE

A method for inspecting a substrate with a multi-layer reflection film reflecting EUV light,
5 includes
imaging the substrate while moving the substrate at a first speed using a first inspection device, to detect an amplitude defect and acquire a coordinate of the amplitude defect in a first
10 coordinate system;
imaging the substrate while moving the substrate at a second speed using a second inspection device, to detect a phase defect and acquire a coordinate of the phase defect in a second
15 coordinate system;
transforming the coordinate of the amplitude defect from the first coordinate system to the second coordinate system; and
imaging the coordinates of the amplitude
20 and phase defects in the second coordinate system using the second inspection device while moving the substrate at a third speed lower than the first and second speeds or while stopping the movement, to re-acquire the coordinates of the amplitude and phase
25 defects.

Fig. 8